

Fig. 1 Absorbance spectra (CHCl_3) of **1** (black) and **2** (red). Inset shows the absorbance and photoluminescence in the quinacridone region.

Comparison of normalized absorbance spectra of 300 nm thin films of dendrimers **1** and **2** to solution spectra confirms non-aggregating chromophore cores brought about by dendron-induced site-isolation (Fig. 2). Decreasing PL λ_{max} (Table 1) and narrower peak widths in thin film PL spectra for dendrimers **1** and **2** indicate decreased amounts of red-shifted (excimer) emission with increasing generation. Interestingly, the PL λ_{max} of both **1** and **2** are blue-shifted compared to the *t*Bu[G3] quinacridone dendrimer reported previously by us,² although the PL efficiencies are somewhat lower. Although the cinnamate dendrons provide physical encapsulation of the chromophores so that aggregation is prevented, it is likely that the dendrons do not spatially isolate the chromophores at sufficient distances to prevent self-quenching which lowers the PL efficiency.

The 300 nm thin films of dendrimers **1** and **2** were subjected to irradiation ($\lambda = 310$ nm, 6 nm slits) using a 75 W Xe arc lamp. The solid state [2 + 2] photodimerization of cinnamic acid and its derivatives is easily monitored by changes in the UV absorbance ($\lambda_{\text{max}} = 310\text{--}315$ nm).^{19–21} Continuous irradiation clearly showed a decrease in the cinnamate peaks in the UV for both **1** (30% overall decrease of 292 nm, λ_{max}) and **2** (40% overall decrease at 292, λ_{max}) after 90 minutes (Fig. 3). The decrease in cinnamate absorbance is most likely due to both *E* → *Z* isomerization as well as [2 + 2] photodimerization. During wet development (CHCl_3 for 3 minutes), a major portion of the film of **1** washed away leaving only 28% of the original absorbing cinnamate peak, while the film of **2** exhibited no change in absorbance subsequent to wet development. These results were the same even after extended wet

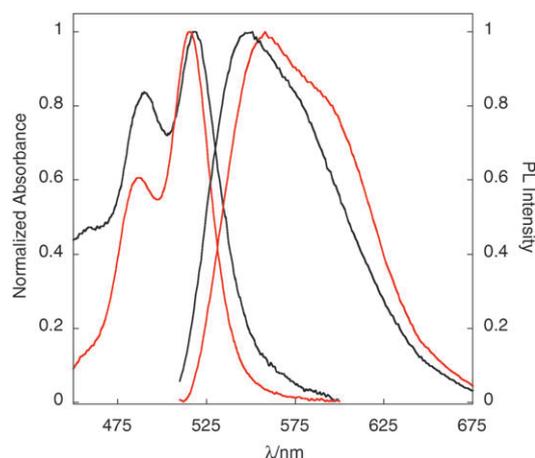


Fig. 2 Thin film (300 nm) absorbance and photoluminescence of **1** (red) and **2** (black).

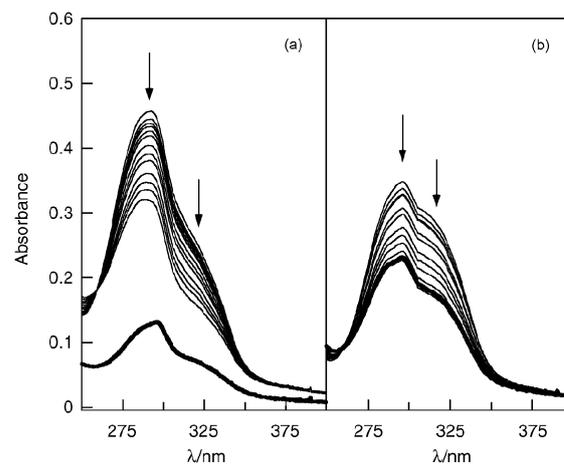


Fig. 3 Absorbance monitoring of crosslinking for (a) **1** and (b) **2** in 300 nm thin films. The dark lines are the spectra measured following wet development in CHCl_3 .

development (18 hours) for **2**. Hence, dendrimer **1** was only moderately successful in achieving a crosslinked film, while **2** formed an insoluble network. Longer irradiation times provided similar results with incomplete crosslinking of **1** in all cases. Several trials determined that at least a 40% loss of cinnamate absorbance was necessary to form an insoluble network for dendrimer **2**. This 40% loss corresponded to *ca.* 60–90 minutes of irradiation depending on film thickness (thicker films required longer irradiation times).

Photoluminescence measurements of dendrimer **2** in 300 nm films indicated an integrated loss of emission of *ca.* 20% after

Table 1 Photophysical characterization of **1** and **2** in CHCl_3 solution and thin film (in parentheses)

	MW/g mol ⁻¹	$\lambda_{\text{max,Abs}}/\text{nm}$	$\lambda_{\text{max,PL}}/\text{nm}$	$10^{-4} \epsilon_{\lambda_{\text{max}}}/\text{M}^{-1} \text{cm}^{-1}$	Φ_{fl}^a	Film PL efficiency ^b
DIQA	452.6	524 (498)	537 (594)	1.79	0.85	1
[G1], 1	1485.7	512 (516)	526 (558)	1.78	0.86	4.1
[G2], 2	2903.3	512 (519)	525 (551)	1.68	1.0	6.4
<i>t</i> Bu[G3] ²	5259.4	513 (516)	526 (567)	1.78	1.0	6.8

^a Measured *versus* a fluorescein standard ($\Phi_{\text{fl}} = 0.95$) 0.1 M aq. NaOH solution. ^b Measured by integrating the corrected PL spectrum ($\lambda_{\text{ex}} = 470$ nm) and dividing by the absorbance at 470 nm. This value was then divided by the analogous value for a **DIQA** film.

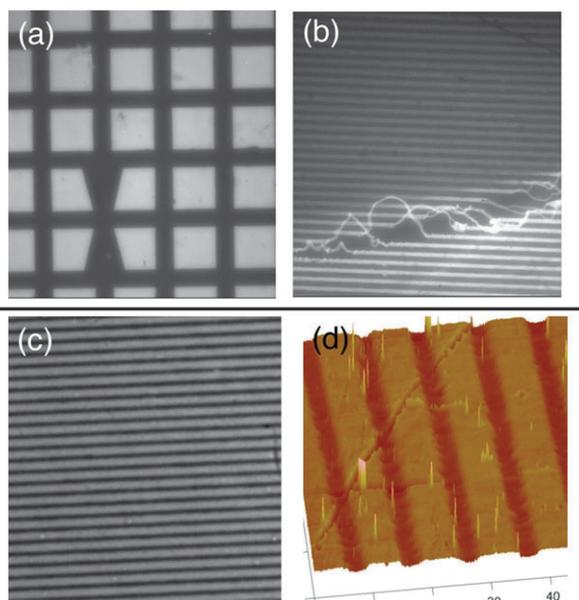


Fig. 4 Fluorescence microscopy images (a), (b), and (c) of patterned dendrimer **2**: (a) was made from TEM grids (*ca.* 85 μm feature sizes), while (b) and (c) are 5 μm lines; (b) shows an area in which the dendrimer has become delaminated and then re-adsorbed to the surface; (c) is 5 μm lines patterned on a *ca.* 6 nm thin film; (d) is an AFM image (full images in ESI[†]) of 5 μm patterned lines of dendrimer **2** on a *ca.* 6 nm thin film.

crosslinking and wet development. This corresponded to a similar 20% decrease in quinacridone absorbance during crosslinking (ESI[†]), suggesting that PL loss was solely due to degradation of the film during crosslinking and that loss of emission due to red-shifting was negligible. Since the bulk of the site-isolation properties of the material remain intact, observed loss in emission is not detrimental to the usefulness of the material in luminescent thin film architectures.

We next produced features from our 300 nm thick dendrimer thin films with pattern sizes ranging from 5 to 85 μm . Films (with *ca.* 85 μm feature sizes) were produced by irradiation (310 nm for 90 minutes) of a film masked with a transmission electron microscopy (TEM) copper grid and subsequent wet development in CHCl_3 . Patterns of dendrimer **2** visualized under a fluorescence microscope (535 nm excitation filter; 615 nm emission filter) exhibited resolved lines with sharp edges (Fig. 4a). These positive tone images have dark areas with no emissive material and light areas of patterned dendrimer. Patterns were produced with *ca.* 5 μm features using a Ronchi ruling (5 μm chrome lines on glass) as a photomask (Fig. 4b). Irradiation times were increased to *ca.* 3 h to account for the low transparency of glass at 310 nm (<10%). Image (b) also shows an area where dendrimer desorption and subsequent readsorption occurred. Remarkably, the crosslinked dendrimer network remained intact in all areas and no disruption of the integrity of the material was observed, indicating a high tensile strength.

Using the conditions for crosslinking determined by the experiments on the 300 nm films, we next patterned the ultra thin films (*ca.* 6 nm) of **2** using a Ronchi ruling mask and

characterized them by fluorescence microscopy and AFM. Fluorescence microscopy images of the patterned 6 nm films (Fig. 4c) are identical to those obtained after patterning 300 nm films (Fig. 4b). However, differences were observed by AFM. Whereas the 300 nm films were found to contain channels after patterning and wet development (ESI[†]), the ultra thin films showed no evidence of channels within the patterned rows (Fig. 4d). We believe that this is due to complete polymerization through the entire thickness of the 6 nm film. The similar thickness of the ultra thin film before and after crosslinking (*ca.* 6 nm), as well as the similar RMS surface roughness, is a further evidence of complete polymerization. In the 300 nm films, the majority of material is removed upon wet development due to incomplete polymerization.

Dendrimers can simultaneously serve multiple roles in a complex system due to their varied yet discrete architecture. The dendrimers presented herein contain all the necessary components that render them easily processed, patternable, emissive materials for the fabrication of stand-alone emissive thin film light sources. These materials indicate enhanced utility for dendrimers in OLEDs and other solution-processed, multilayer luminescent devices.

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Notes and references

- 1 J. Shi and C. W. Tang, *Appl. Phys. Lett.*, 1997, **70**, 1665.
- 2 A. Ortiz, W. H. Flora, G. D. D'Ambruoso, N. R. Armstrong and D. V. McGrath, *Chem. Commun.*, 2005, 444.
- 3 W. H. Flora, H. K. Hall and N. R. Armstrong, *J. Phys. Chem. B*, 2003, **107**, 1142.
- 4 S. E. Shaheen, B. Kippelen, N. Peyghambarian, J. F. Wang, J. D. Anderson, E. A. Mash, P. A. Lee, N. R. Armstrong and Y. Kawabe, *J. Appl. Phys.*, 1999, **85**, 7939.
- 5 G. D. D'Ambruoso and D. V. McGrath, *Adv. Polym. Sci.*, 2008, **214**, 87.
- 6 A. Adronov and J. M. J. Fréchet, *Chem. Commun.*, 2000, 1701.
- 7 V. Balzani, P. Ceroni, M. Maestri, C. Saudan and V. Vicinelli, *Top. Curr. Chem.*, 2003, **228**, 159.
- 8 C. S. Cameron and C. B. Gorman, *Adv. Funct. Mater.*, 2002, **12**, 17.
- 9 C. B. Gorman and J. C. Smith, *Acc. Chem. Res.*, 2001, **34**, 60.
- 10 S. Hecht and J. M. J. Fréchet, *Angew. Chem., Int. Ed.*, 2001, **40**, 74.
- 11 J. Kofoed and J.-L. Reymond, *Curr. Opin. Chem. Biol.*, 2005, **9**, 656.
- 12 A. W. Freeman, J. M. J. Fréchet, S. C. Koene and M. E. Thompson, *Polym. Prepr. (Am. Chem. Soc., Div. Polym. Chem.)*, 1999, **40**, 1246.
- 13 A. W. Freeman, S. C. Koene, P. R. L. Malenfant, M. E. Thompson and J. M. J. Fréchet, *J. Am. Chem. Soc.*, 2000, **122**, 12385.
- 14 P. Furuta, J. Brooks, M. E. Thompson and J. M. J. Fréchet, *J. Am. Chem. Soc.*, 2003, **125**, 13165.
- 15 M. Kawa and J. M. J. Fréchet, *Chem. Mater.*, 1998, **10**, 286.
- 16 C. C. Kwok and M. S. Wong, *Chem. Mater.*, 2002, **14**, 3158.
- 17 M. Halim, J. N. G. Pillow, I. D. W. Samuel and P. L. Burn, *Adv. Mater.*, 1999, **11**, 371.
- 18 J. M. Lupton, L. R. Hemmingway, I. D. W. Samuel and P. L. Burn, *J. Mater. Chem.*, 2000, **10**, 867.
- 19 H. I. Bernstein and W. C. Quimby, *J. Am. Chem. Soc.*, 1943, **65**, 1845.
- 20 M. D. Cohen, G. M. J. Schmidt and F. I. Sonntag, *J. Chem. Soc.*, 1964, 2000.
- 21 H. Stobbe, *Ber. Dtsch. Chem. Ges.*, 1919, **52**, 666.